

Notice of References Cited	Application/Control No. 10/690,573	Applicant(s)/Patent Under Reexamination SONG ET AL.	
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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-6,914,641	07-2005	Choo et al.	349/38
*	C	US-5,838,314	11-1998	Neel et al.	725/8
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*	E	US-5,963,689	10-1999	Hesselbom, Hjalmar	385/53
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*	G	US-6,057,896	05-2000	Rho et al.	349/42
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	U	Je-Hsiung Lan et al., 'Planarization technology Of a Si:H TFTs for Am-LCDs', July 1988, SPIE Vol. 3421, SPIE conference On Display Technologies II, Taipei, Taiwan, pages 170-182. <i>(already mailed 9/01/05 see EDAN)</i>			
	V	Phillip E. Garrou et al., ' Stress-Buffer and Passivation Processes for SI and GaAs IC's and Passive Components Using Photosensitive BCB: Process Technology and Reliability Data ' IEEE Transactions on Advanced Packaging , Vol. 22 No.3 August 1999, pages <i>already mailed 9/01/05 - see EDAN)</i>			
	W	M.J. Radler et al., " A2.4 : Cyclotene Advanced Electronics resins for High-Aperture AMLCD Applications ", 1996 , SID 96 Applications Digest pages 33-36 <i>already mailed 09/01/05 - see EDAN</i>			
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

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	J	US-			
	K	US-			
	L	US-			
	M	US-			

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